

IN THE CLAIMS

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of claims:

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1. (Original) A depolarization method comprising the step of selectively exposing a portion of a fabrication tool to a plasma for a selected time interval wherein said selected time interval has a duration sufficient to reduce a polarization of said portion of said fabrication tool whereby interference with a motion of a device being processed by said fabrication tool is not observed.
 2. (Currently Amended) The method of claim 1 wherein said step of selectively exposing said portion of said fabrication tool includes selecting for exposing said portion of said fabrication tool at preselected intervals of time, and exposing said ~~structure~~ portion if interference with said motion of said device is observed.
 3. (Original) The method of claim 2 further comprising the step of detecting said interference with said motion of said device.
 4. (Original) The method of claim 3 wherein said step of detecting said interference with said motion comprises step of detecting a misalignment of said device with respect to said portion of said fabrication tool.
 5. (Original) The method of claim 1 wherein said portion of said fabrication tool comprises an insulating pad.
 6. (Original) The method of claim 1 wherein said plasma comprises a plasma formed from a noble gas.

7. (Original) The method of claim 6 wherein said noble gas is selected from the group consisting of xenon and argon.
8. (Original) The method of claim 1 further comprising the step of generating said plasma with a plasma flood gun.
9. (Original) The method of claim 8 wherein said plasma flood gun includes an arc discharge.
10. (Original) The method of claim 9 wherein said arc discharge is struck between a hot filament cathode and an anode.
11. (Original) The method of claim 10 wherein said arc discharge has a voltage drop between said cathode and said anode of between ten and thirty volts.
12. (Original) The method of claim 8 wherein said step of exposing said portion of said fabrication tool comprises the step of positioning said portion of said fabrication tool in proximity to an aperture of said plasma flood gun.
13. (Original) The method of claim 1 wherein said preselected time interval is preselected from the range of five to ten minutes.
14. (Original) A depolarization process comprising the steps of:
- positioning an insulating pad in proximity to an aperture of a plasma flood gun (PFG);
 - and exposing said insulating pad to a plasma from said PFG for a selected interval of time wherein said selected interval of time has a duration sufficient to reduce a polarization of said structure whereby interference with a motion of a device supported on said insulating pad is not observed.

15. (Original) The process of claim 14 wherein said plasma is formed from a noble gas.

16. (Original) The process of claim 15 wherein said noble gas is selected from a group consisting of xenon and argon.

17. (Original) The process of claim 14 further comprising the step of generating said plasma by striking an arc discharge in a gas supplied to said PFG.

18. (Original) A depolarization method comprising the step of selectively exposing a portion of a fabrication tool to a plasma for a selected time interval.

19. (Currently Amended) The method of claim 18 wherein said step of selectively exposing a said portion of said fabrication tool includes exposing said portion ~~of said portion~~ of said fabrication tool if interference with a motion of a device being processed in said fabrication tool is observed.

20. (Original) The method of claim 18 wherein said plasma comprises a plasma formed from a noble gas.

21. (Original) The method of claim 18 further comprising the step of generating said plasma with a plasma flood gun.

22. (Original) The method of claim 18 wherein said portion of said fabrication tool comprises an insulating pad.

23. (Currently Amended) The ~~process~~ method of claim 19 wherein said interference with said motion of said device is indicated by a misalignment of said device with respect to said portion of said fabrication tool.

24. (Currently Amended) The ~~process~~ method of claim 18 wherein said portion of said fabrication tool is in a vacuum region of said fabrication tool.
